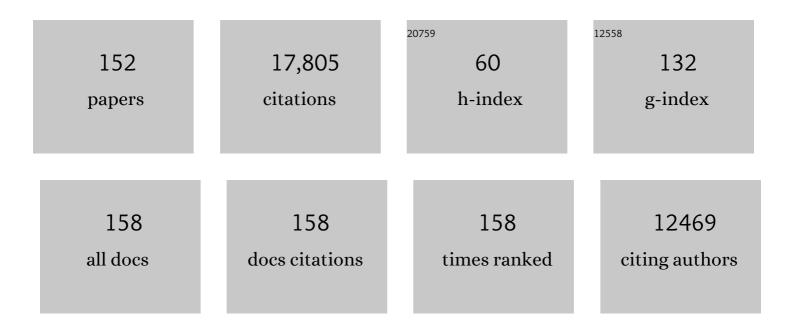
## Stephen Y Chou

List of Publications by Year in descending order

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#	Article	IF	CITATIONS
1	Imprint of subâ€⊋5 nm vias and trenches in polymers. Applied Physics Letters, 1995, 67, 3114-3116.	1.5	2,565
2	Nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1996, 14, 4129.	1.6	1,577
3	Sub-10 nm imprint lithography and applications. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2897.	1.6	1,033
4	Fabrication of 5nm linewidth and 14nm pitch features by nanoimprint lithography. Applied Physics Letters, 2004, 84, 5299-5301.	1.5	564
5	Deterministic hydrodynamics: Taking blood apart. Proceedings of the National Academy of Sciences of the United States of America, 2006, 103, 14779-14784.	3.3	540
6	Statics and Dynamics of Single DNA Molecules Confined in Nanochannels. Physical Review Letters, 2005, 94, 196101.	2.9	480
7	Ultrafast and direct imprint of nanostructures in silicon. Nature, 2002, 417, 835-837.	13.7	445
8	Singleâ€domain magnetic pillar array of 35 nm diameter and 65 Gbits/in.2density for ultrahigh density quantum magnetic storage. Journal of Applied Physics, 1994, 76, 6673-6675.	1.1	366
9	A Silicon Single-Electron Transistor Memory Operating at Room Temperature. Science, 1997, 275, 649-651.	6.0	363
10	Imprint lithography with sub-10 nm feature size and high throughput. Microelectronic Engineering, 1997, 35, 237-240.	1.1	353
11	Graphene Transistors Fabricated via Transfer-Printing In Device Active-Areas on Large Wafer. Nano Letters, 2007, 7, 3840-3844.	4.5	333
12	Silicon single-electron quantum-dot transistor switch operating at room temperature. Applied Physics Letters, 1998, 72, 1205-1207.	1.5	322
13	Fabrication of 10 nm enclosed nanofluidic channels. Applied Physics Letters, 2002, 81, 174-176.	1.5	312
14	Micro- and nanofluidics for DNA analysis. Analytical and Bioanalytical Chemistry, 2004, 378, 1678-1692.	1.9	292
15	Roller nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3926.	1.6	286
16	Fabrication of 70 nm channel length polymer organic thin-film transistors using nanoimprint lithography. Applied Physics Letters, 2002, 81, 4431-4433.	1.5	278
17	Nanolithographically defined magnetic structures and quantum magnetic disk (invited). Journal of Applied Physics, 1996, 79, 6101.	1.1	261
18	Lithographically induced self-assembly of periodic polymer micropillar arrays. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 3197.	1.6	256

#	Article	IF	CITATIONS
19	Observation of quantum effects and Coulomb blockade in silicon quantumâ€dot transistors at temperatures over 100 K. Applied Physics Letters, 1995, 67, 938-940.	1.5	226
20	Fabrication of large area subwavelength antireflection structures on Si using trilayer resist nanoimprint lithography and liftoff. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 2874.	1.6	220
21	Lithographically induced self-construction of polymer microstructures for resistless patterning. Applied Physics Letters, 1999, 75, 1004-1006.	1.5	205
22	Gradient nanostructures for interfacing microfluidics and nanofluidics. Applied Physics Letters, 2002, 81, 3058-3060.	1.5	199
23	Wafer-scale patterning of sub-40 nm diameter and high aspect ratio (>50:1) silicon pillar arrays by nanoimprint and etching. Nanotechnology, 2008, 19, 345301.	1.3	197
24	Large area high density quantized magnetic disks fabricated using nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3825.	1.6	183
25	Nanogap Detector Inside Nanofluidic Channel for Fast Real-Time Label-Free DNA Analysis. Nano Letters, 2008, 8, 1472-1476.	4.5	182
26	Nano-compact disks with 400 Gbit/in2 storage density fabricated using nanoimprint lithography and read with proximal probe. Applied Physics Letters, 1997, 71, 3174-3176.	1.5	181
27	Three-dimensional cavity nanoantenna coupled plasmonic nanodots for ultrahigh and uniform surface-enhanced Raman scattering over large area. Optics Express, 2011, 19, 3925.	1.7	166
28	A room-temperature silicon single-electron metal–oxide–semiconductor memory with nanoscale floating-gate and ultranarrow channel. Applied Physics Letters, 1997, 70, 850-852.	1.5	142
29	6 nm half-pitch lines and 0.04 µm2static random access memory patterns by nanoimprint lithography. Nanotechnology, 2005, 16, 1058-1061.	1.3	142
30	Large Enhancement of Upconversion Luminescence of NaYF <sub>4</sub> :Yb <sup>3+</sup> /Er <sup>3+</sup> Nanocrystal by 3D Plasmonic Nanoâ€Antennas. Advanced Materials, 2012, 24, OP236-41.	11.1	140
31	Fabrication of circular optical structures with a 20 nm minimum feature size using nanoimprint lithography. Applied Physics Letters, 2000, 76, 673-675.	1.5	139
32	Nanoscale silicon field effect transistors fabricated using imprint lithography. Applied Physics Letters, 1997, 71, 1881-1883.	1.5	136
33	Single hole quantum dot transistors in silicon. Applied Physics Letters, 1995, 67, 2338-2340.	1.5	134
34	Enhancement of Immunoassay's Fluorescence and Detection Sensitivity Using Three-Dimensional Plasmonic Nano-Antenna-Dots Array. Analytical Chemistry, 2012, 84, 4489-4495.	3.2	132
35	Reflective polarizer based on a stacked double-layer subwavelength metal grating structure fabricated using nanoimprint lithography. Applied Physics Letters, 2000, 77, 927.	1.5	127
36	Sub-20-nm Alignment in Nanoimprint Lithography Using Moiré Fringe. Nano Letters, 2006, 6, 2626-2629.	4.5	115

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37	Fabrication of 60-nm transistors on 4-in. wafer using nanoimprint at all lithography levels. Applied Physics Letters, 2003, 83, 1632-1634.	1.5	113
38	Direct nanoimprint of submicron organic light-emitting structures. Applied Physics Letters, 1999, 75, 2767-2769.	1.5	112
39	Direct three-dimensional patterning using nanoimprint lithography. Applied Physics Letters, 2001, 78, 3322-3324.	1.5	111
40	Single Sub-20 nm Wide, Centimeter-Long Nanofluidic Channel Fabricated by Novel Nanoimprint Mold Fabrication and Direct Imprinting. Nano Letters, 2007, 7, 3774-3780.	4.5	111
41	Ultrathin, high-efficiency, broad-band, omni-acceptance, organic solar cells enhanced by plasmonic cavity with subwavelength hole array. Optics Express, 2013, 21, A60.	1.7	109
42	Nanoimprint Lithography and Lithographically Induced Self-Assembly. MRS Bulletin, 2001, 26, 512-517.	1.7	107
43	Study of nanoscale magnetic structures fabricated using electron-beam lithography and quantum magnetic disk. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 3695.	1.6	102
44	Crossing microfluidic streamlines to lyse, label and wash cells. Lab on A Chip, 2008, 8, 1448.	3.1	101
45	Sacrificial polymers for nanofluidic channels in biological applications. Nanotechnology, 2003, 14, 578-583.	1.3	98
46	Air Cushion Press for Excellent Uniformity, High Yield, and Fast Nanoimprint Across a 100 mm Field. Nano Letters, 2006, 6, 2438-2441.	4.5	94
47	Sub-10 nm Self-Enclosed Self-Limited Nanofluidic Channel Arrays. Nano Letters, 2008, 8, 3830-3833.	4.5	91
48	Size effects on switching field of isolated and interactive arrays of nanoscale singleâ€domain Ni bars fabricated using electronâ€beam nanolithography. Journal of Applied Physics, 1994, 76, 6679-6681.	1.1	90
49	Multilayer resist methods for nanoimprint lithography on nonflat surfaces. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3922.	1.6	86
50	Hydrodynamic metamaterials: Microfabricated arrays to steer, refract, and focus streams of biomaterials. Proceedings of the National Academy of Sciences of the United States of America, 2008, 105, 7434-7438.	3.3	86
51	Fabrication of a new broadband waveguide polarizer with a double-layer 190 nm period metal-gratings using nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 2957.	1.6	85
52	Giant and uniform fluorescence enhancement over large areas using plasmonic nanodots in 3D resonant cavity nanoantenna by nanoimprinting. Nanotechnology, 2012, 23, 225301.	1.3	83
53	Large area direct nanoimprinting of SiO[sub 2]–TiO[sub 2] gel gratings for optical applications. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 660.	1.6	82
54	Multilevel nanoimprint lithography with submicron alignment over 4 in. Si wafers. Applied Physics Letters, 2001, 79, 845-847.	1.5	81

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55	Air bubble formation and dissolution in dispensing nanoimprint lithography. Nanotechnology, 2007, 18, 025303.	1.3	79
56	Observation of dynamic behavior of lithographically induced self-assembly of supramolecular periodic pillar arrays in a homopolymer film. Applied Physics Letters, 2001, 79, 1688-1690.	1.5	73
57	Ultrasensitive Ebola Virus Antigen Sensing via 3D Nanoantenna Arrays. Advanced Materials, 2019, 31, e1902331.	11.1	71
58	Ultrafast patterning of nanostructures in polymers using laser assisted nanoimprint lithography. Applied Physics Letters, 2003, 83, 4417-4419.	1.5	69
59	Fabrication of large area 100 nm pitch grating by spatial frequency doubling and nanoimprint lithography for subwavelength optical applications. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19. 2816.	1.6	67
60	Controlling polarization of vertical avity surfaceâ€emitting lasers using amorphous silicon subwavelength transmission gratings. Applied Physics Letters, 1996, 69, 7-9.	1.5	66
61	Improved nanofabrication through guided transient liquefaction. Nature Nanotechnology, 2008, 3, 295-300.	15.6	66
62	Quantification of magnetic force microscopy using a micronscale current ring. Applied Physics Letters, 1997, 70, 2043-2045.	1.5	62
63	Extraordinary light transmission through opaque thin metal film with subwavelength holes blocked by metal disks. Optics Express, 2011, 19, 21098.	1.7	59
64	Fabrication of nanoscale gratings with reduced line edge roughness using nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 2089.	1.6	55
65	Fabrication of single-domain magnetic pillar array of 35 nm diameter and 65 Cbits/in.2 density. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 3639.	1.6	53
66	Ultrahigh resolution magnetic force microscope tip fabricated using electron beam lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1993, 11, 2570.	1.6	51
67	Fabrication of planar quantum magnetic disk structure using electron beam lithography, reactive ion etching, and chemical mechanical polishing. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2850.	1.6	51
68	Fabrication and characterization of room temperature silicon single electron memory. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2840.	1.6	51
69	Plasmonic Nanocavity Organic Lightâ€Emitting Diode with Significantly Enhanced Light Extraction, Contrast, Viewing Angle, Brightness, and Lowâ€Glare. Advanced Functional Materials, 2014, 24, 6329-6339.	7.8	51
70	Dynamic modeling and scaling of nanostructure formation in the lithographically induced self-assembly and self-construction. Applied Physics Letters, 2003, 82, 3200-3202.	1.5	50
71	Electrohydrodynamic instability of a thin film of viscoelastic polymer underneath a lithographically manufactured mask. Journal of Non-Newtonian Fluid Mechanics, 2005, 125, 91-99.	1.0	49
72	10 nm Si pillars fabricated using electron-beam lithography, reactive ion etching, and HF etching. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1993, 11, 2524.	1.6	48

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73	Triangular Profile Imprint Molds in Nanograting Fabrication. Nano Letters, 2004, 4, 341-344.	4.5	48
74	Electrostatic Force-Assisted Nanoimprint Lithography (EFAN). Nano Letters, 2005, 5, 527-530.	4.5	48
75	Pattern transfer fidelity of nanoimprint lithography on six-inch wafers. Nanotechnology, 2003, 14, 33-36.	1.3	47
76	Subwavelength amorphous silicon transmission gratings and applications in polarizers and waveplates. Applied Physics Letters, 1995, 67, 742-744.	1.5	46
77	Self-formation of sub-60-nm half-pitch gratings with large areas through fracturing. Nature Nanotechnology, 2007, 2, 545-548.	15.6	46
78	100 nm period gratings produced by lithographically induced self-construction. Nanotechnology, 2003, 14, 786-790.	1.3	44
79	Tunable Liquid Crystal-Resonant Grating Filter Fabricated by Nanoimprint Lithography. IEEE Photonics Technology Letters, 2007, 19, 1457-1459.	1.3	42
80	Perpendicular quantized magnetic disks with 45 Gbits on a 4×4 cm2 area. Journal of Applied Physics, 1999, 85, 5534-5536.	1.1	41
81	Room-temperature Si single-electron memory fabricated by nanoimprint lithography. Applied Physics Letters, 2003, 83, 2268-2270.	1.5	38
82	In situ real time process characterization in nanoimprint lithography using time-resolved diffractive scatterometry. Applied Physics Letters, 2004, 85, 4166-4168.	1.5	37
83	Highâ€modulationâ€depth and shortâ€cavityâ€length silicon Fabry–Perot modulator with two grating Bragg reflectors. Applied Physics Letters, 1996, 68, 170-172.	1.5	36
84	Fabrication of a Molecular Self-Assembled Monolayer Diode Using Nanoimprint Lithography. Nano Letters, 2003, 3, 1687-1690.	4.5	36
85	Fabrication of nanocontacts for molecular devices using nanoimprint lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2002, 20, 665.	1.6	35
86	Study of magnetic properties of magnetic force microscopy probes using micronscale current rings. Journal of Applied Physics, 1997, 81, 5026-5028.	1.1	32
87	Cylindrically symmetric electrohydrodynamic patterning. Physical Review E, 2004, 70, 041601.	0.8	31
88	High-efficiency and high-speed silicon metal–semiconductor–metal photodetectors operating in the infrared. Applied Physics Letters, 1997, 70, 753-755.	1.5	29
89	Plasmonic Bar-Coupled Dots-on-Pillar Cavity Antenna with Dual Resonances for Infrared Absorption and Sensing: Performance and Nanoimprint Fabrication. ACS Nano, 2014, 8, 2618-2624.	7.3	29
90	Effects of bar length on switching field of nanoscale nickel and cobalt bars fabricated using lithography. Journal of Applied Physics, 1996, 80, 5205-5208.	1.1	28

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91	The fabrication of periodic metal nanodot arrays through pulsed laser melting induced fragmentation of metal nanogratings. Nanotechnology, 2009, 20, 285310.	1.3	28
92	Applications of excimer laser in nanofabrication. Applied Physics A: Materials Science and Processing, 2010, 98, 9-59.	1.1	28
93	Sub-10-nm Wide Trench, Line, and Hole Fabrication Using Pressed Self-Perfection. Nano Letters, 2008, 8, 1986-1990.	4.5	26
94	Quantum magnetic disk. Journal of Magnetism and Magnetic Materials, 1996, 155, 151-153.	1.0	25
95	Enhancement and Electric Charge-Assisted Tuning of Nonlinear Light Generation in Bipolar Plasmonics. Nano Letters, 2014, 14, 2822-2830.	4.5	25
96	Lithographically induced self-assembly of microstructures with a liquid-filled gap between the mask and polymer surface. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 2741.	1.6	24
97	Single electron and hole quantum dot transistors operating above 110 K. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2865.	1.6	23
98	Molecular alignment in submicron patterned polymer matrix using nanoimprint lithography. Applied Physics Letters, 2000, 77, 166-168.	1.5	23
99	Large area 50nm period grating by multiple nanoimprint lithography and spatial frequency doubling. Applied Physics Letters, 2007, 90, 043118.	1.5	23
100	Singleâ€electron Coulomb blockade in a nanometer fieldâ€effect transistor with a single barrier. Applied Physics Letters, 1992, 61, 1591-1593.	1.5	22
101	Ultrafast direct imprinting of nanostructures in metals by pulsed laser melting. Nanotechnology, 2010, 21, 045303.	1.3	21
102	Printing of sub-20 nm wide graphene ribbon arrays using nanoimprinted graphite stamps and electrostatic force assisted bonding. Nanotechnology, 2011, 22, 445301.	1.3	21
103	Fabrication and performance of thin amorphous Si subwavelength transmission grating for controlling vertical cavity surface emitting laser polarization. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena. 1996, 14, 4055.	1.6	20
104	Tunable External Cavity Laser With a Liquid-Crystal Subwavelength Resonant Grating Filter as Wavelength-Selective Mirror. IEEE Photonics Technology Letters, 2007, 19, 1099-1101.	1.3	20
105	Internal emission metalâ€semiconductorâ€metal photodetectors on Si and GaAs for 1.3 μm detection. Applied Physics Letters, 1995, 66, 2673-2675.	1.5	19
106	Ultrafast and selective reduction of sidewall roughness in silicon waveguides using self-perfection by liquefaction. Nanotechnology, 2009, 20, 345302.	1.3	19
107	Fabrication of sub-50 nm finger spacing and width high-speed metal–semiconductor–metal photodetectors using high-resolution electron beam lithography and molecular beam epitaxy. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1991, 9, 2920.	1.6	18
108	32 GHz metalâ€semiconductorâ€metal photodetectors on crystalline silicon. Applied Physics Letters, 1992, 61, 1760-1762.	1.5	18

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109	Effect of bar width on magnetoresistance of nanoscale nickel and cobalt bars. Journal of Applied Physics, 1997, 81, 5461-5463.	1.1	18
110	Nanoimprint mold fabrication and replication by room-temperature conformal chemical vapor deposition. Applied Physics Letters, 2007, 90, 203115.	1.5	17
111	Double 15-nm-wide metal gates 10 nm apart and 70 nm thick on GaAs. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1990, 8, 1919.	1.6	16
112	Growth of Straight Silicon Nanowires on Amorphous Substrates with Uniform Diameter, Length, Orientation, and Location Using Nanopatterned Host-Mediated Catalyst. Nano Letters, 2011, 11, 5247-5251.	4.5	16
113	Fabrication of sub-25 nm diameter pillar nanoimprint molds with smooth sidewalls using self-perfection by liquefaction and reactive ion etching. Nanotechnology, 2008, 19, 455301.	1.3	15
114	Fabrication of a 60â€nmâ€Diameter Perfectly Round Metalâ€Dot Array over a Large Area on a Plastic Substrate Using Nanoimprint Lithography and Selfâ€Perfection by Liquefaction. Small, 2010, 6, 1242-1247.	5.2	15
115	Silicon nanopillar anodes for lithium-ion batteries using nanoimprint lithography with flexible molds. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2014, 32, .	0.6	15
116	Polarimetry of thin metal transmission gratings in the resonance region and its impact on the response of metal-semiconductor-metal photodetectors. Applied Physics Letters, 1997, 70, 2673-2675.	1.5	13
117	Alkylsiloxane self-assembled monolayer formation guided by nanoimprinted Si and SiO2 templates. Applied Physics Letters, 2006, 89, 153121.	1.5	13
118	Self-aligned fabrication of 10 nm wide asymmetric trenches for Si/SiGe heterojunction tunneling field effect transistors using nanoimprint lithography, shadow evaporation, and etching. Journal of Vacuum Science & Technology B, 2009, 27, 2790-2794.	1.3	12
119	Current fluctuations in doubleâ€barrier quantum well resonant tunneling diodes. Applied Physics Letters, 1991, 59, 1105-1107.	1.5	10
120	Fabrication of high aspect ratio metal nanotips by nanosecond pulse laser melting. Nanotechnology, 2008, 19, 345303.	1.3	10
121	Application of amorphous silicon subwavelength gratings in polarization switching vertical-cavity surface-emitting lasers. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2864.	1.6	9
122	Filling of nano-via holes by laser-assisted direct imprint. Microelectronic Engineering, 2006, 83, 1547-1550.	1.1	9
123	In situ real time monitoring of nanosecond imprint process. Applied Physics Letters, 2006, 89, 073107.	1.5	9
124	A novel method for fabricating sub-16 nm footprint T-gate nanoimprint molds. Nanotechnology, 2009, 20, 185302.	1.3	9
125	Response to "Comment on †Fabrication of a Molecular Self-Assembled Monolayer Diode Using Nanoimprint Lithography'― Nano Letters, 2004, 4, 535-535.	4.5	8
126	Materials Aspects in Micro- and Nanofluidic Systems Applied to Biology. MRS Bulletin, 2006, 31, 108-113.	1.7	8

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127	Self-limited self-perfection by liquefaction for sub-20 nm trench/line fabrication. Nanotechnology, 2009, 20, 465305.	1.3	7
128	Integration of metallic nanostructures in fluidic channels for fluorescence and Raman enhancement by nanoimprint lithography and lift-off on compositional resist stack. Microelectronic Engineering, 2012, 98, 693-697.	1.1	7
129	Nanolithographically defined magnetic structures. Scripta Metallurgica Et Materialia, 1995, 33, 1537-1544.	1.0	6
130	RIMS (real-time imprint monitoring by scattering of light) study of pressure, temperature and resist effects on nanoimprint lithography. Nanotechnology, 2007, 18, 065304.	1.3	6
131	The anti-lotus leaf effect in nanohydrodynamic bump arrays. New Journal of Physics, 2010, 12, 085008.	1.2	6
132	Effects of sample size and field orientation on pseudo-Hall voltage in micronscale nickel thin-film squares. Journal of Applied Physics, 1997, 81, 5475-5477.	1.1	5
133	Quantized patterning using nanoimprinted blanks. Nanotechnology, 2009, 20, 155303.	1.3	3
134	Nanoimprint Lithography. Nanostructure Science and Technology, 2003, , 15-23.	0.1	3
135	Fabrication and properties of visible-light subwavelength amorphous silicon transmission gratings. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2879.	1.6	2
136	Group velocities in coplanar strip transmission lines on Si and Si/SiO2/Si substrates measured using differential electroâ€optic sampling. Applied Physics Letters, 1996, 69, 2861-2863.	1.5	1
137	Nonmonotonic length dependence of switching field of nanolithographically defined single-domain nickel and cobalt bars (abstract). Journal of Applied Physics, 1996, 79, 5067.	1.1	1
138	A Spectrum-narrowed, Wavelength and Temperature Stabilized Broad Area Laser Using a Subwavelength Resonant Grating Filter Feedback. , 2006, , .		1
139	Nanoimprint (Technology, Tools, Applications and Commercialization) And New Technologies Beyond. , 2007, , .		1
140	Drive-Current Tuning of Self-Oscillation Frequency of External Cavity VCSEL. , 2011, , .		1
141	Nanoscale negative-tone quantized patterning by novel selective electrochemical etching of a nanoimprinted sub-200 nm bimetallic tile array. Nanotechnology, 2012, 23, 355303.	1.3	1
142	Electric Current Tuning the Self-Oscillation Frequency of EC-VCSELs. IEEE Photonics Technology Letters, 2013, 25, 1707-1710.	1.3	1
143	Plasmonic nanocavity organic solar cells with highly enhanced power conversion efficiency, broad-band, and omni-acceptance. , 2014, , .		1
144	Subwavelength Optical Elements (SOEs) and Nanofabrications – A path to integrate optical communication components on a chip. , 2003, , .		1

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145	Large-area Metal Grid Ultraviolet Filter Fabricated by Nanoimprint Lithography. , 2007, , .		0
146	Subwavelength Optical Elements and Nanoimprint Technology for Optical System on Chip. , 2007, , .		0
147	A path to integrate optical communication components on a chip. , 2003, , .		0
148	InGaAs/InP Subwavelength Grating Filters for the Mid-Infrared. , 2010, , .		0
149	Blocker size effects on extraordinary light transmission through subwavelength holes in opaque thin metal film. , 2012, , .		0
150	Shaping Fluorescence Emission Spectrum Using Plasmonic Nanocavities Created by Double-Nanoimprint Technique. , 2012, , .		0
151	Strong Enhancement of Upconversion Luminescence by 3-Dimensional Plasmonic Nano-Cavities. , 2012, ,		0
152	Ultrafast Metal-Semiconductor-Metal Photodetectors with Nanometer Scale Finger Spacing and Width. , 1993, , .		0